



# EUROSOI-ULIS 2026

## PROGRAM



UNIVERSIDAD  
DE GRANADA



<b>WEDNESDAY, 20th May 2026</b>	
08:30 – 09:00	Welcome and Opening Session
09:00 – 09:40	<b>Invited Talk 1 - Tianchun Ye (Chinese Academy of Sciences) The Key Role of FD-SOI Technology in China Chair: Prof. Sorin Cristoloveanu</b>
<b>09:40 – 11:00</b>	<b>SESSION 1 – RF and Millimeter-Wave Devices Chair: Prof. Bogdan Cretu</b>
09:40 – 10:00	<b>Can resistivity increase with doping? Weijia Song (Université catholique de Louvain)</b>
10:00 – 10:20	<b>Cryogenic RF Characterisation of Passive Components for VCO and PLL Design in P28 FD-SOI for Quantum Computing Applications Victor Sabiá Pereira Carpes (CEA-Leti &amp; Grenoble INP - CROMA)</b>
10:20 – 10:40	<b>Role of Interface Degradation and Overlap Capacitance on the RF Performance of Self-Aligned Gate InGaAs MOSFETs Mu Yu Chen (National Yang Ming Chiao Tung University)</b>
10:40 – 11:00	<b>Opposite-Polarity Fixed Charges in BEOL Dielectrics for Interface Passivation on HR Silicon Substrates Jingru Shen (Université catholique de Louvain)</b>
11:00 – 11:30	Coffee Break
<b>11:30 – 13:10</b>	<b>SESSION 2 – FD-SOI Reliability Chair: Prof. Monserrat Nafria</b>
11:30 – 11:50	<b>BOX CREEP: A Mechanical Booster for Next-Generation FDSOI Maxime Sauvagnac (CEA-LETI)</b>
11:50 – 12:10	<b>Strain engineering of thin monocrystalline Si films on 8-inch wafers using Surface Activated Hot Bonding Quentin Guillet (Univ. Grenoble Alpes, CEA-LETI)</b>
12:10 – 12:30	<b>Impact of source/drain dopant implantation and spike annealing on electrical parameters of 25 nm FDSOI n- MOSFETs Alexandre Vernhet (CEA / LETI)</b>

12:30 – 12:50	<p><b>Impact of Device Position within the Silicon Active Area on Self-Heating and Thermal Coupling in FD-SOI Transistors</b></p> <p>Nika Sahebghalam (Université catholique de Louvain)</p>
12:50 – 13:10	<p><b>Analysis of uncertainties in the Self-Heating Extraction by RF technique in FD-SOI Transistors</b></p> <p>Eric Vandermolen (ICTEAM, UCLouvain)</p>
13:10 – 14:30	Lunch Break
14:30 – 15:10	<p><b>Invited Talk 2 - John Cressler (Georgia Tech)</b></p> <p><b>Using SiGe Electronics and Photonics in Space Systems</b></p> <p>Chair: Prof. Carlos Marquez</p>
<b>15:10 – 16:10</b>	<p><b>SESSION 3 - Advanced Fabrication</b></p> <p>Chair: Prof. Joao Antonio Martino</p>
15:10 – 15:30	<p><b>Mandrel material selection as prerequisite for SADP implementation at the 10 nm FD-SOI node</b></p> <p>Sylvain Beaurepaire (Univ. Grenoble Alpes, CEA-Leti)</p>
15:30 – 15:50	<p><b>Implantation- and Bonding-Free Multilayer SOI Fabrication via Annealing-Oxidation</b></p> <p>Jungchul Lee (Korea Advanced Institute of Science and Technology)</p>
15:50 – 16:10	<p><b>Fabrication and characterisation of GeSn devices for quantum applications</b></p> <p>Nikolay Petkov (Munster Technological University and Tyndall National Institute)</p>
16:10 – 16:40	Coffee Break
<b>16:40 – 18:00</b>	<p><b>SESSION 4 - Cryogenic Device Physics</b></p> <p>Chair: Prof. Carlos Sampedro</p>
16:40 – 17:00	<p><b>Impact of silicon thickness on the carrier mobility of 28 nm FDSOI MOSFET from room temperature to cryogenic regime</b></p> <p>Jaime Calcade Rodrigues (Centro Universitário FEI)</p>
17:00 – 17:20	<p><b>Demonstration of Trap Recovery by In-Situ Annealing in 28nm FD-SOI MOSFETs at Cryogenic Temperatures</b></p> <p>Vincent Dieuzeide (ICTEAM Institute, Université catholique de Louvain)</p>

17:20 – 17:40	<b>Cryogenic DC and Low-Frequency Noise Investigation of Vertical Gate-All-Around Silicon Nanowire pMOSFET Arrays</b> Abderrahim Tahiat (Normandie Univ, ENSICAEN, UNICAEN, CNRS, GREYC)
17:40 – 18:00	<b>Ultra-low threshold voltage shifts in passivated GaN-on-Si HEMTs under cryogenic operation</b> Siwei Zhou (University of Liverpool)
19:45 – 21:00	<b>Cultural Guided Tour</b>
21:00	<b>Welcome Cocktail at Carmen de la Victoria</b>

<b>THURSDAY, 21st May 2026</b>	
09:00 – 09:40	<b>Invited Talk 3 – Saptarshi Das (PennState)</b> <b>High-performance complementary 2D transistors and 3D integration for advanced logic</b> Chair: Prof. Alexander Zaslavsky
<b>09:40 – 11:00</b>	<b>SESSION 5 - 2D Materials</b> Chair: Prof. Robert Mroczynsky
09:40 – 10:00	<b>Experimental Demonstration of 2D Core-Shell Junctionless FET</b> Mingyi Du (School of Electronic Science and Engineering, Nanjing University)
10:00 – 10:20	<b>In-depth TCAD study of stacked MoS<sub>2</sub> channel FETs based on a channel-last integration</b> Rihab Chouk (Univ. Grenoble Alpes, CEA, Leti)
10:20 – 10:40	<b>Ab-initio transport simulations of Dirac Source FETs based on van der Waals Heterojunctions between graphene and functionalized graphene</b> Khanh-Duy Nguyen (DPIA, University of Udine)
10:40 – 11:00	<b>DFT based layered dielectric model for MoS<sub>2</sub>/SiO<sub>2</sub> structure</b> Ruben Ortega Lopez (University of Granda, CTIC UGR)

11:00 – 11:30	Coffee Break
<b>11:30 – 13:10</b>	<b>SESSION 6 - TCAD and beyond CMOS</b> Chair: Prof. Giorgio Fagas
11:30 – 11:50	<b>Forksheet versus Nanosheet Transistors: A Multi-Dimensional Scaling Comparison of Electrostatic Performance and Thermal Robustness</b> Joao Martino (LSI/PSI/USP)
11:50 – 12:10	<b>Impact of Forksheet Transistor on Low-Dropout Regulator Performance</b> Henrique De Mare Corazza (LSI/PSI/USP, University of Sao Paulo)
12:10 – 12:30	<b>Real Time Simulations of Advanced MOSFETs</b> Avanish Singh (IIT Hyderabad)
12:30 – 12:50	<b>Understanding room-temperature electrical characterizations of FDSOI spin qubit devices via TCAD simulations</b> Fatima Zahrae Tijent (Univ. Grenoble Alpes, CEA, Leti)
12:50 – 13:10	<b>Impact of RDF in the channel on the On-current of GAA nanosheet transistors through Monte Carlo simulations</b> Rhaycen Prates (Centro Universitário FEI)
13:10 – 14:30	Lunch Break
14:30 – 15:10	<b>Invited Talk 4 - Hanwool Yeon Gwangju (GIST)</b> <b>Synergistic Metallization Strategies for Heterogeneous Integration in Artificial Intelligence Hardware</b> Chair: Prof. Valeri Afanasev
<b>15:10 – 16:30</b>	<b>SESSION 7 - Contacts</b> Chair: Prof. Pierpaolo Palestri
15:10 – 15:30	<b>Reduced metal gate height and in-situ doped faceted raised source and drain regions for advanced RF FD-SOI devices</b> Yinyin Zhang Fu (CEA-Leti, UCLouvain)
15:30 – 15:50	<b>Low-temperature dielectric for BEOL integration of Si-based RFETs</b> Katrin Pinggen (NaMLab gGmbH)

15:50 – 16:10	<b>ITO/TiW Contacts for Transparent FDSOI CMOS</b> Doga Selin Memikoglu (KTH Royal Institute of Technology, School of EECS)
16:10 – 16:30	<b>Contact Punch-Through Failure Mitigation in Advanced FD-SOI Nodes</b> Emmanuel Petitprez (Univ. Grenoble Alpes, CEA-Leti)
16:30 – 17:00	Coffee Break and <b>Poster Session</b> (Poster details in <a href="#">Appendix I</a> )
17:00 – 19:00	<b>Poster Session</b> (Poster details in <a href="#">Appendix I</a> )
21:00	<b>Gala Dinner at Hotel Gran Luna</b>

FRIDAY, 22nd May 2026	
09:00 – 09:40	<b>Invited Talk 5 - Andrea Capasso (INL)</b> <b>2D memristors for memory and neuromorphic applications</b> Chair: Prof. Francis Balestra
<b>09:40 – 11:00</b>	<b>SESSION 8 - Memristors, ReRAM</b> Chair: Prof. Vihar Georgiev
09:40 – 10:00	<b>Investigation of 1T1R Memristive Structures and Physics-Based Extension of the Stanford Model Including the Change of Filament Geometry</b> Nadine Dersch (THM University of Applied Sciences)
10:00 – 10:20	<b>Interface-Engineered Cryogenic Memristors Enabling Sub-100 <math>\mu</math>V Scalable Qubit Biasing</b> Erbing Hua (Delft University of Technology)
10:20 – 10:40	<b>Al-rich AlN thin films deposited by Molecular Beam Epitaxy on SiNx ReRAMs</b> Alexandros Eleftherios Mavropoulis (NCSR Demokritos)
10:40 – 11:00	<b>Improving the conductance ratio of mechanically-exfoliated MoS<sub>2</sub> and WS<sub>2</sub> based memristors</b> Deianira Fejzaj (Technische Universitaet Dresden)

11:00 – 11:30	Coffee Break
<b>11:30 – 11:35</b>	<b>FET 100 - Celebrating 100 years of the FET</b> Prof. Hiroshi Iwai (Eminent Lecturer of IEEE EDS)
<b>11:35 – 13:15</b>	<b>SESSION 9 - Emerging Devices (FET 100 - Celebrating 100 years of the FET)</b> Chair: Prof. Hiroshi Iwai
11:35 – 11:55	<b>The Ultimate Field Effect Transistor: GAIA MOSFET</b> Francis Balestra (Grenoble INP-CNRS)
11:55 – 12:15	<b>Enhancing Negative Differential Transconductance by Ultra-Thin Ge on SOI</b> Walter M. Weber (TU Wien)
12:15 – 12:35	<b>Split MLP Architectures for Accurate Joint Modeling of drain and gate currents in FD-SOI Transistors</b> Yusra Rachidi (CEA-LETI)
12:35 – 12:55	<b>From FD-SOI to MoS2 MOSFETs: Coupling Mechanisms</b> Xuan Zhang (GIICS Guangdong Greater Bay Area Institute of Integrated Circuit and System / Nanjing University)
12:55 – 13:15	<b>Single Trap and Low Frequency 1/f Noise Modeling in MOSFETs with Dirac Materials or 2D Semiconductor Channel</b> Pierpaolo Palestri (University of Modena and Reggio Emilia)
13:15 – 14:30	Lunch Break
<b>14:30 – 15:50</b>	<b>SESSION 10 - Emerging Memory Technologies</b> Chair: Dr. Andrea Capasso
14:30 – 14:50	<b>Ultra-low-power in-memory computing based on spin-orbit ferroelectric devices for artificial intelligence and logic</b> Emanuel Vazquez (Spintec, UGA, CEA, CNRS)
14:50 – 15:10	<b>Ultra-low power Ru/TiOx/TiN RRAM structures for applications in neuromorphic computing</b> Piotr Jezak (Warsaw University of Technology)
15:10 – 15:30	<b>Positive-Bias Erase Schemes for FeFETs: Switching Comparison Between FDSOI and Bulk devices</b> Dominik Martin Kleimaier (GlobalFoundries)

15:30 – 15:50	<b>Probabilistic bits based on Ag/SiOx/BE threshold switching memristors</b> Piotr Wiśniewski (Warsaw University of Technology)
15:50 – 16:20	Closing Remarks
16:20 – 17:00	Coffee Break

# Appendix I

16:30 – 19:00	Poster Session
	<p><b>P1: Analysis and Optimization of a Planar SOI RFET for Dynamic Reconfigurable Logic</b> João Antonio Martino (Universidade de São Paulo (USP))</p>
	<p><b>P2: VTH Extraction in VGT-Normalized AlGaN/GaN HEMTs</b> Maria Glória Caño de Andrade (São Paulo State University)</p>
	<p><b>P3: Vertical Capacitance and Edge-Field Engineering in 4H-SiC MOS Capacitors</b> Maria Gloria Cano de Andrade (São Paulo State University)</p>
	<p><b>P4: Relocating Dopants from Si to SiO<sub>2</sub>: About Fundamentals and Applications of Modulation Acceptor Doping of Silicon</b> Daniel Hiller (IAP Technical University Bergakademie Freiberg)</p>
	<p><b>P5: Simulating the Impact of Activation Functions on the Performance of 1T1R RRAM-Based Neural Networks Under Cycle-to-Cycle Variability Conditions</b> Alan Blumenstein (THM University of Applied Sciences)</p>
	<p><b>P6: Enhancing High-Temperature Analog Performance of MOSFETs Through a Half-Diamond Layout Hardness-by-Design Approach</b> Salvador Gimenez (FEI University Center)</p>
	<p><b>P7: A Scalable Time-Multiplexed Biasing Architecture for FDSOI Spin Qubits</b> Antoine Faurie (CEA/LETI)</p>
	<p><b>P8: Co-Integration of Tunnel FET and FinFET for Hybrid LDO Circuit Design</b> Pedro Henrique Madeira (FESJ-Unesp)</p>

<p><b>P9: Study of Variability in Threshold Voltage Engineering for Nanosheet MOSFETs using TCAD</b> Zih Fei Chen (Institute of Microelectronics Engineering, National Cheng Kung University)</p>
<p><b>P10: Al/SnO<sub>2</sub>/ITO-Based Memristive Soft-Threshold Neuron (MSTN) for Low-Power Neuromorphic Computing</b> Abhishek Acharya (Svmit surat)</p>
<p><b>P11: Bias-dependent contact resistance model in Graphene on-Insulator FETs</b> Nikolaos Mavredakis (Universitat Autònoma de Barcelona)</p>
<p><b>P12: Feasibility Study of a Damage- and Pressure-Free AC Pseudo-MOS Method Using a Mercury Probe</b> Ruka Yokoyama (Faculty of Engineering Science, Kansai University)</p>
<p><b>P13: Optimization of Hybrid Source and Drain Extension Metal in AlGa<sub>N</sub>/Ga<sub>N</sub> HEMTs: A Simulation and Experimental Study</b> Howie Tseng (National Yang Ming Chiao Tung University, and Universidad de Granada)</p>
<p><b>P14: Impact of Random Dopant Fluctuation in Stacked Drain Extended NSFETs</b> Abhishek Acharya (S. V. National Institute of Technology Surat India)</p>
<p><b>P15: Performance Assessment of Spacer Engineered InGaAs NSFETs: A Physical Insight</b> Abhishek Acharya (S. V. National Institute of Technology Surat India)</p>
<p><b>P16: Physical Electro-thermal Modelling of HfO<sub>2</sub>-based Nanoscale Memristor for Artificial Synapses</b> Ankit Dixit (James Watt School of Engineering, University of Glasgow)</p>
<p><b>P17: Properties of Ru/Hf<sub>1-x</sub>ZrxO<sub>2</sub>/p-Si MOS Gate Stack Structures Deposited by Pulsed-DC Sputtering Using a Periodic Layer-by-Layer Deposition Process</b> Rezwana Sultana (Warsaw University of Technology, Institute of Microelectronics and Optoelectronics)</p>

	<p><b>P18: Area-Dependent Switching and Synaptic Behavior in Al/TiOx/TiN devices</b>  Karimul Islam (Warsaw University of Technology, Institute of Microelectronics and Optoelectronics)</p>
	<p><b>P19: Mixed Finite Element Method for Quantum Dots Array Simulation</b>  Yingjia Gao (University of Glasgow)</p>
	<p><b>P20: Experimental Nanosheet Transistors: Temperature and Inversion-Regime Effects on a Two-Stage Operational Transconductance Amplifier</b>  Thainá Guimarães (University of Sao Paulo)</p>
	<p><b>P21: Impact of Vertical Nanowire VFET Structural Asymmetry on Static and Dynamic Performance of Two-Stage OTA</b>  Vanessa Silva (USP University of Sao Paulo)</p>
	<p><b>P22: Unified Physics-Based Verilog-A Compact Model of Independent-Gate Reconfigurable FETs: Dual- and Triple-Gate Architectures</b>  Ananya Karmakar (THM University of Applied Sciences)</p>
	<p><b>P23: Interplay of Hot Carrier Degradation and Device Variability in NSFETs: A TCAD Study</b>  Soumya Panda (IHT Unistuttgart &amp; NIT Rourkela)</p>
	<p><b>P24: Electronic Structure of W-doped In<sub>2</sub>O<sub>3</sub> BEOL Oxide Semiconductors</b>  John Robertson (Cambridge University)</p>
	<p><b>P25: Absence of P-doping by Localized Acceptor Polarons in TeO<sub>2</sub> Semiconductors</b>  John Robertson (Cambridge University)</p>
	<p><b>P26: Band gap and Defects of AlScN ferroelectrics for BEOL non-volatile memories</b>  Ruyue Cao (Cambridge University)</p>
	<p><b>P27: Electronic Structure of IGZO and its Hydrogen Defects</b>  Ruyue Cao (Cambridge University)</p>
	<p><b>P28: Origin of ferroelectricity in HfO<sub>2</sub>/ZrO<sub>2</sub> thin films without depolarization</b>  Ruyue Cao (University of Cambridge)</p>

	<p><b>P29: Temperature Influence on Single Trap Junctionless Nanowire Transistors Low-Frequency Noise</b> Rodrigo Doria (Centro Universitário FEI)</p>
	<p><b>P30: Experimental Emulation and Functional Validation of a Dual-Doped Reconfigurable FET for Hardware Security</b> Antonio Manuel Hervas Ramirez (CITIC UGR)</p>
	<p><b>P31: Stack-in-Pillar, a CFET strategy to implement IC at advanced technology nodes</b> Hugo Lozano (Institute of Microelectronics of Barcelona)</p>
	<p><b>P32: A compact model of perovskite memristors inspired by the Stanford RRAM model</b> Bitania Shiferaw Mengesha (Universitat Rovira i Virgili)</p>
	<p><b>P33: DC characterization of BEOL metallic layers in silicon technologies for cryogenic microelectronics</b> Salvador Mir Bernardo (Univ. Grenoble Alpes, CNRS, Grenoble-INP, TIMA, France)</p>
	<p><b>P34: SOI based Nanowire Field-Effect Transistor Biosensors with Diamond-Like Carbon Modification</b> Hanlin Long (Forschungszentrum Jülich GmbH)</p>
	<p><b>P35: Temperature Dependent Carrier Transport Mechanisms in WSe<sub>2</sub></b> Stephen O'Sullivan (MicroNano systems, Tyndall National Institute, University College Cork)</p>
	<p><b>P36: Analytical Modeling of Rectifiers for Radio-Frequency Energy Harvesting</b> Kimberlly Pedroso (Pontifical Catholic University of São Paulo)</p>
	<p><b>P37: Impact of neglecting the bias dependence of access resistances on DC and 1/f noise parameter extraction</b> Bogdan Cretu (Normandie Univ, ENSICAEN, UNICAEN, CNRS, GREYC)</p>
	<p><b>P38: Non-Quasi Static Small Signal Model of a Nanosheet FET for High-Frequency Application: Capturing the Role of the Corner Rounding</b> Vihar Georgiev (University of Glasgow)</p>

	<p><b>P39: Demonstration of the Novel Junctionless Complementary FET</b> Vihar Georgiev (University of Glasgow)</p>
	<p><b>P40: Analysis of Self Heating in SiC-6H and Al<sub>2</sub>O<sub>3</sub> Substrate Platforms with SiO<sub>2</sub> Buried Oxide Integration on AlGaN HEMT</b> Pankaj Kumar (Dhirubhai Ambani University)</p>
	<p><b>P41: Impact of BOX scaling and ground plane on 1/f noise in FDSOI pMOSFET</b> Prabhat Khedgarkar (Indian Institute of Technology Ropar)</p>
	<p><b>P42: Optimization of Magnetron-Sputtered Al Thin Films for Controlled Surface Roughness in RRAM Applications</b> Michał Jarosik (Warsaw University of Technology, Centre for Advanced Materials and Technologies CEZAMAT)</p>
	<p><b>P43: Dielectric BD in FDSOI Transistors: circuital compact model and Impact on digital Circuits</b> Montserrat Nafria (Autonoma University of Barcelona)</p>
	<p><b>P44: Statistical Robustness Analysis of Diamond MOSFETs under High-Dose Gamma Radiation in 350 nm Bulk CMOS Technology</b> Vinicius Vono Peruzzi (CTI Renato Archer)</p>
	<p><b>P45: Statistical Robustness Analysis of MOSFETs with Different Layout Styles Under Gamma Radiation Using the Coefficient of Variation</b> Vinicius Vono Peruzzi (CTI Renato Archer)</p>
	<p><b>P46: Study of the annealing effect on Al<sub>2</sub>O<sub>3</sub>-based 1T1R RRAM cell</b> Aleksander Malkowski (Warsaw University of Technology, Center for Advanced Materials and Technology CEZAMAT)</p>
	<p><b>P47: Operation of Junctionless Nanowire Transistors-Based Common Source Current Mirror at Cryogenic Temperatures</b> Renan Doria (PUC-SP)</p>